IN THE CLAIMS:

1. (Currently Amended) A manufacturing apparatus comprising:

a loading chamber;

a transporting chamber coupled to the loading chamber;

a first film formation chamber coupled to the transporting chamber through the loading chamber;

a plurality of second film formation chambers coupled to the transporting chamber;

a first processing chamber coupled to the transporting chamber,

a second processing chamber coupled to the transporting chamber,

wherein the first film formation chamber comprises a spin coater for forming a layer with a polymeric material,

wherein the first processing chamber is capable of generating a plasma for performing dry etching to remove a portion of the layer formed with a polymeric material,

wherein each of the plurality of second film formation chambers is coupled to a vacuum pump,

wherein each of the plurality of second film formation chambers comprises:

an alignment means for performing a position alignment of a mask and a substrate;

a substrate holding means;

an evaporation source holder; and

a means for moving the evaporation source holder;

wherein the evaporation source holder comprises:

a container that seals an evaporation material;

a means for heating the container; and

a shutter provided over the container;

wherein the second processing chamber is coupled to a vacuum pump,

wherein a plurality of plate heaters are disposed within the processing chamber so as to overlap with each other and have gaps therebetween, and

wherein the second processing chamber can perform a vacuum heating on a plurality of substrates, and

wherein each of the plurality of substrates is held by substrate holders attached to first

and second panel heaters holding the plurality of plate heaters.

2. (Previously presented) A manufacturing apparatus according to claim 1, wherein the means for moving the evaporation source holder functions to move the evaporation source holder in an x-axis direction at a certain pitch, and functions to move the evaporation source holder in a y-axis direction at a certain pitch.

3. (Previously presented) A manufacturing apparatus according to claim 2, wherein the evaporation source holder is rotated when switching between the x-axis direction and the y-axis direction.

4. (Original) A manufacturing apparatus according to claim 1, wherein a hole of an opening surface area S2, which is smaller than an opening surface area S1 of the container, is opened in the shutter.

5. (Previously presented) A manufacturing apparatus according to claim 1, wherein a film thickness monitor is provided adjacent to the evaporation source holder.

6-13. (Canceled)

14. (Currently Amended) A manufacturing apparatus comprising:

a transporting chamber;

a loading chamber coupled to the coupled to the transporting chamber;

a first film formation chamber coupled to the transporting chamber through the loading chamber, wherein the first film formation chamber comprises a spin coater for forming a layer with a polymeric material;

a second film formation chamber coupled to the transporting chamber, wherein the second film formation chamber comprises an evaporation source holder for forming an electroluminescence layer over a substrate;

a first processing chamber coupled to the transporting chamber, wherein the first processing chamber is capable of generating a plasma for performing dry etching to remove a

portion of the layer formed with a polymeric material; and

a second processing chamber coupled to the transporting chamber, wherein the second processing chamber is capable of performing a vacuum heating on a plurality of substrates simultaneously, and

wherein each of the plurality of substrates is held by substrate holders attached to first and second panel heaters holding a plurality of plate heaters.

15. (Previously presented) A manufacturing apparatus according to claim 14, wherein the evaporation source holder comprises a heater.

16. (Previously presented) A manufacturing apparatus according to claim 14, wherein the evaporation source holder comprises a shutter having a hole.

17. (Previously presented) A manufacturing apparatus according to claim 14, wherein a film thickness monitor is provided adjacent to the evaporation source holder.

18. (Previously presented) A manufacturing apparatus according to claim 14, wherein the electroluminescence layer comprises at least one selected from the group consisting of a hole injecting layer, a hole transporting layer, a light emitting layer, an electron transporting layer, and an electron injecting layer.

19. (Currently Amended) A manufacturing apparatus comprising:

a transporting chamber;

a loading chamber coupled to the coupled to the transporting chamber;

a first film formation chamber coupled to the transporting chamber through the loading chamber, wherein the first film formation chamber comprises a spin coater for forming a layer with a polymeric material;

a [[film]] second film formation chamber coupled to the transporting chamber, wherein the second film formation chamber comprises an evaporation source holder for forming an electroluminescence layer over a substrate;

a first processing chamber coupled to the transporting chamber, wherein the first

processing chamber is capable of generating a plasma for performing dry etching to remove a portion of the layer formed with a polymeric material; and

a second processing chamber coupled to the transporting chamber, wherein the second processing chamber comprises a plurality of plate heaters held between panel heaters, and is capable of performing a vacuum heating on a plurality of substrates simultaneously, and

wherein a plurality of substrate holders are attached to the panel heaters, and each of the plurality of substrate holders are positioned between two plate heaters.

20. (Previously presented) A manufacturing apparatus according to claim 19, wherein the evaporation source holder comprises a heater.

21. (Previously Presented) A manufacturing apparatus according to claim 19, wherein the evaporation source holder comprises a shutter having a hole.

22. (Previously presented) A manufacturing apparatus according to claim 19, wherein a film thickness monitor is provided adjacent to the evaporation source holder.

23. (Previously presented) A manufacturing apparatus according to claim 19, wherein the electroluminescence layer comprises at least one selected from the group consisting of a hole injecting layer, a hole transporting layer, a light emitting layer, an electron transporting layer, and an electron injecting layer.

24. (Currently Amended) A manufacturing apparatus comprising:

a transporting chamber;

a loading chamber coupled to the coupled to the transporting chamber;

a first film formation chamber coupled to the transporting chamber through the loading chamber, wherein the first film formation chamber comprises a spin coater for forming a layer with a polymeric material;

a second film formation chamber coupled to the transporting chamber, wherein the second film formation chamber comprises an evaporation source holder for forming an electroluminescence layer over a substrate, and a means for moving the evaporation source

holder;

a first processing chamber coupled to the transporting chamber, wherein the first processing chamber is capable of generating a plasma for performing dry etching to remove a portion of the layer formed with a polymeric material; and

a second processing chamber coupled to the transporting chamber, wherein the second processing chamber is capable of performing a vacuum heating on a plurality of substrates simultaneously, and

wherein each of the plurality of substrates is held by substrate holders attached to first and second panel heaters holding a plurality of plate heaters.

25. (Previously presented) A manufacturing apparatus according to claim 24, wherein the means for moving the evaporation source holder functions to move the evaporation source holder in an x-axis direction at a certain pitch, and functions to move the evaporation source holder in a y-axis direction at a certain pitch.

26. (Previously presented) A manufacturing apparatus according to claim 25, wherein the evaporation source holder is rotated when switching between the x-axis direction and the y-axis direction.

27. (Previously presented) A manufacturing apparatus according to claim 24, wherein the evaporation source holder comprises a heater.

28. (Previously presented) A manufacturing apparatus according to claim 24, wherein the evaporation source holder comprises a shutter having a hole.

29. (Previously presented) A manufacturing apparatus according to claim 24, wherein a film thickness monitor is provided adjacent to the evaporation source holder.

30. (Previously presented) A manufacturing apparatus according to claim 24, wherein the electroluminescence layer comprises at least one selected from the group consisting of a hole injecting layer, a hole transporting layer, a light emitting layer, an electron transporting

layer, and an electron injecting layer.

31. (Currently Amended) A manufacturing apparatus comprising:

a transporting chamber;

a loading chamber coupled to the coupled to the transporting chamber;

a first film formation chamber coupled to the transporting chamber through the loading chamber, the first film formation chamber comprises a spin coater for forming a layer with a polymeric material;

a second film formation chamber coupled to the transporting chamber, wherein the second film formation chamber comprises an evaporation source holder for forming an electroluminescence layer over a substrate, and a means for moving the evaporation source holder;

a first processing chamber coupled to the transporting chamber, wherein the first processing chamber is capable of generating a plasma for performing dry etching to remove a portion of the layer formed with a polymeric material; and

a second processing chamber coupled to the transporting chamber, wherein the second processing chamber comprises a plurality of plate heaters held between panel heaters, and is capable of performing a vacuum heating on a plurality of substrates simultaneously, and

wherein a plurality of substrate holders are attached to the panel heaters, and each of the plurality of substrate holders are positioned between two plate heaters.

32. (Previously presented) A manufacturing apparatus according to claim 31, wherein the means for moving the evaporation source holder functions to move the evaporation source holder in an x-axis direction at a certain pitch, and functions to move the evaporation source holder in a y-axis direction at a certain pitch.

33. (Previously presented) A manufacturing apparatus according to claim 32, wherein the evaporation source holder is rotated when switching between the x-axis direction and the y-axis direction.

34. (Previously presented) A manufacturing apparatus according to claim 31, wherein

the evaporation source holder comprises a heater.

35. (Previously presented) A manufacturing apparatus according to claim 31, wherein the evaporation source holder comprises a shutter having a hole.

36. (Previously presented) A manufacturing apparatus according to claim 31, wherein a film thickness monitor is provided adjacent to the evaporation source holder.

37. (Previously presented) A manufacturing apparatus according to claim 31, wherein the electroluminescence layer comprises at least one selected from the group consisting of a hole injecting layer, a hole transporting layer, a light emitting layer, an electron transporting layer, and an electron injecting layer.

38. (Previously presented) A manufacturing apparatus according to claim 1, wherein the plurality of substrates are heated by a thermal radiation of an infrared light.

39. (Previously presented) A manufacturing apparatus according to claim 14, wherein the plurality of substrates are heated by a thermal radiation of an infrared light.

40. (Previously presented) A manufacturing apparatus according to claim 19, wherein the plurality of substrates are heated by a thermal radiation of an infrared light.

41. (Previously presented) A manufacturing apparatus according to claim 24, wherein the plurality of substrates are heated by a thermal radiation of an infrared light.

42. (Previously presented) A manufacturing apparatus according to claim 31, wherein the plurality of substrates are heated by a thermal radiation of an infrared light.

43. (Previously presented) A manufacturing apparatus according to claim 1, wherein the vacuum pump is at least one of a magnetic levitation turbo-molecular pump, a cryopump, and a dry pump.